

Application No. 10/036,469

AMENDMENTS TO THE CLAIMS:

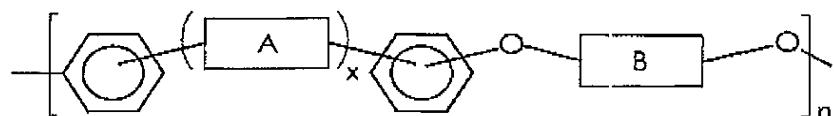
This listing of claims will replace all prior versions, and listings of claims in the application:

LISTING OF CLAIMS:

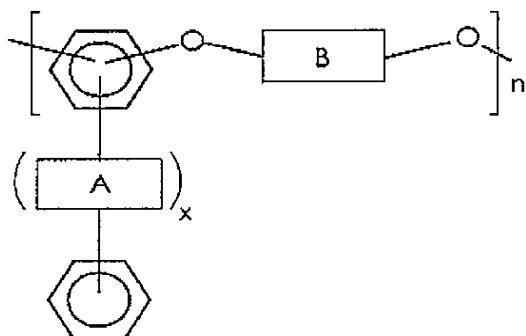
1-9. (Canceled)

Application No. 10/036,469

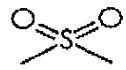
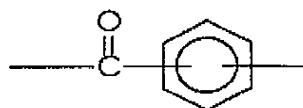
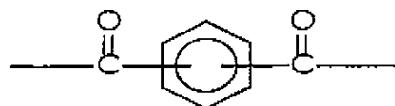
10. (Original) A process which comprises reacting a polymer containing at least some monomer repeat units with haloalkyl substituents thereon and of the formula



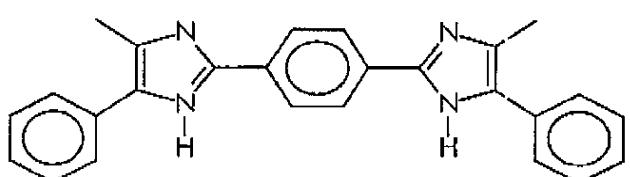
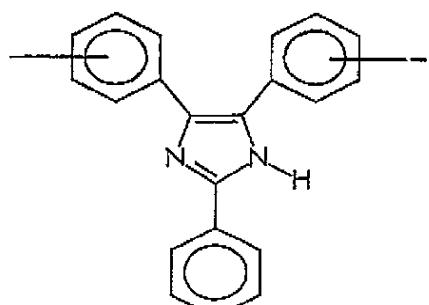
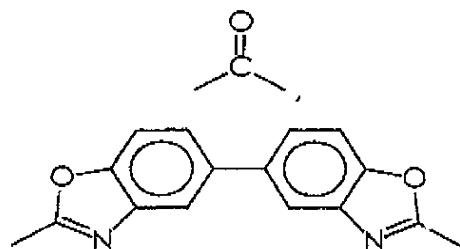
or



wherein x is an integer of 0 or 1, A is

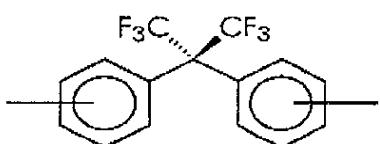


Application No. 10/036,469

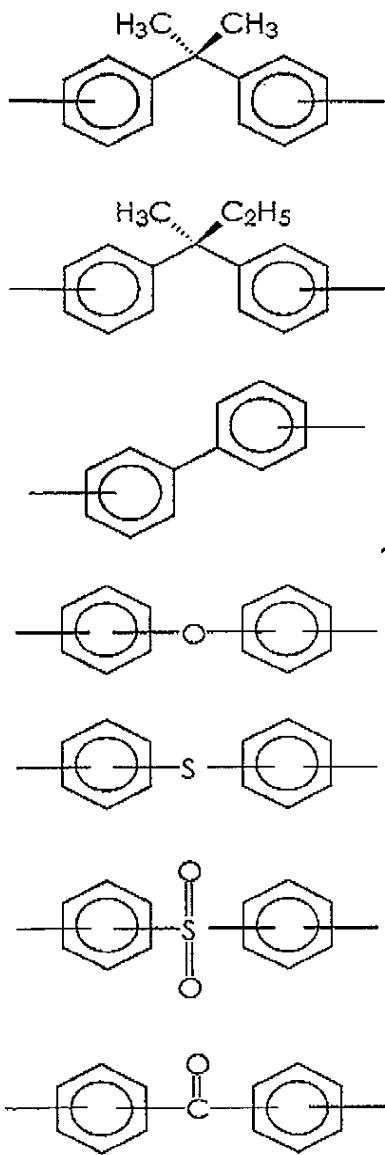


-O-,
-C(CH₃)₂-,

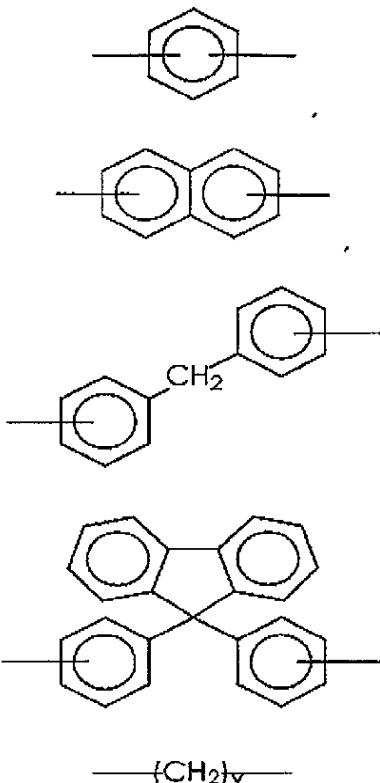
or mixtures thereof, B is



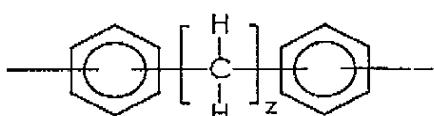
Application No. 10/036,469



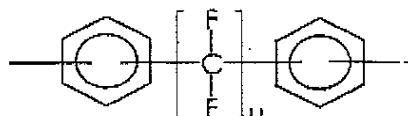
Application No. 10/036,469



wherein v is an integer of from 1 to about 20,

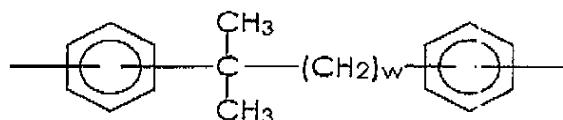
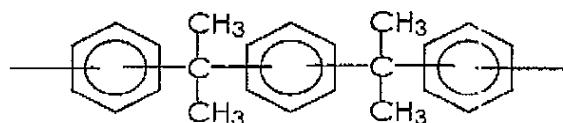
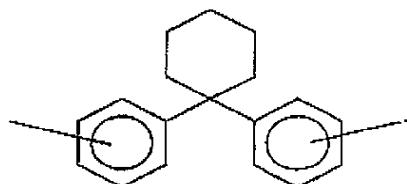
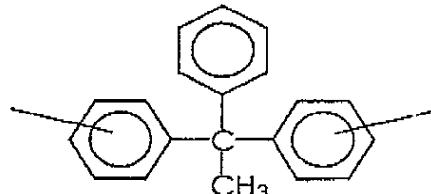


wherein z is an integer of from 2 to about 20,

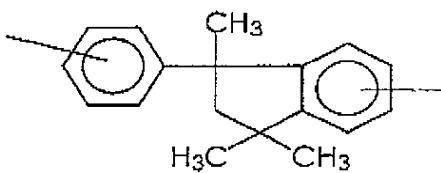


Application No. 10/036,469

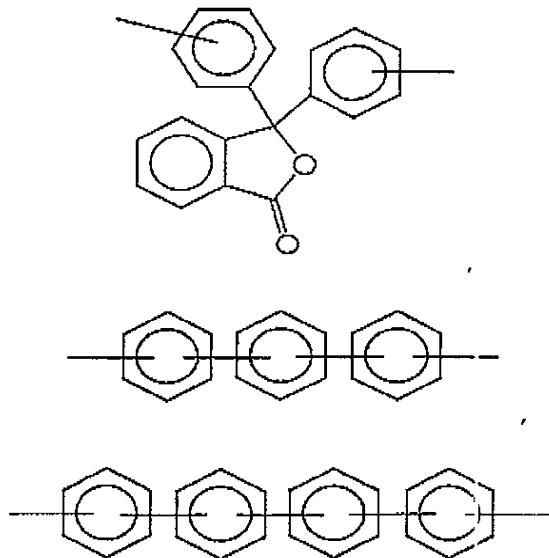
wherein u is an integer of from 1 to about 20,



wherein w is an integer of from 1 to about 20,



Application No. 10/036,469



or mixtures thereof, and n is an integer representing the number of repeating monomer units, with an allyl alcohol salt, thereby forming a photopatternable polymer with allyl ether functional groups corresponding to the selected salt.

11. (Original) A polymer prepared by the process of claim 10.

12. (Original) A process according to claim 10 comprising the further step of reacting the polymer with allyl ether functional groups with a peroxide, thereby forming a photopatternable polymer with epoxy functional groups.

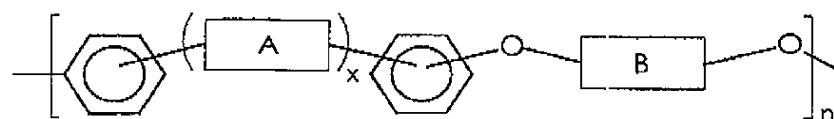
Application No. 10/036,469

13. (Original) A polymer prepared by the process of
claim 12.

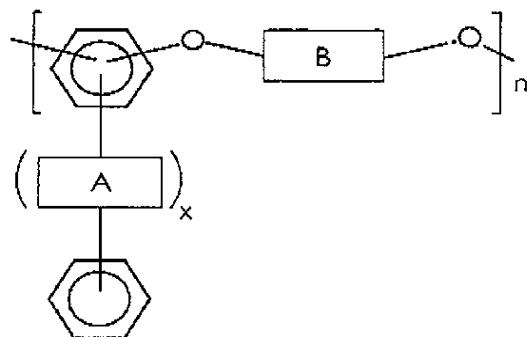
14-15. (Cancelled)

Application No. 10/036,469

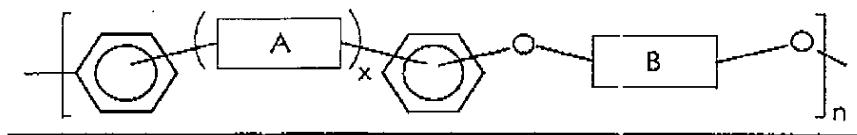
16. (Currently amended) A composition which comprises a crosslinked or chain extended polymer having a backbone of the formula



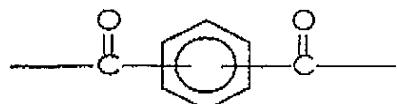
or



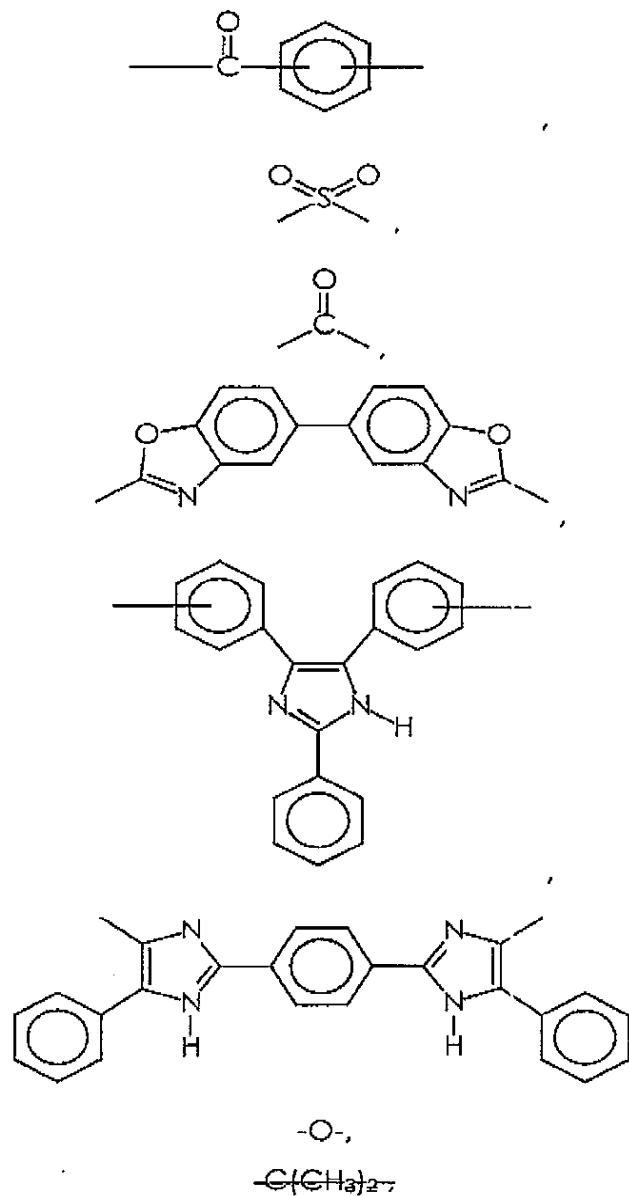
wherein the phenyl groups and the A and B groups can be substituted, wherein x is an integer of 0 or 1 and n is an integer representing the number of repeating monomer units and is at least 2, wherein, when the polymer backbone is of the formula



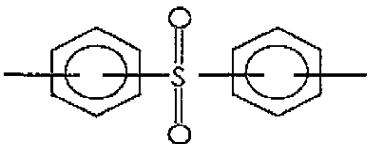
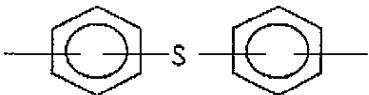
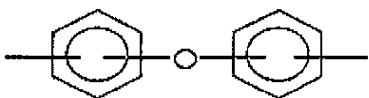
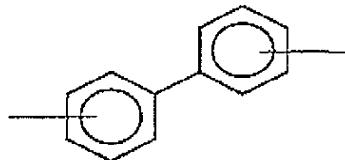
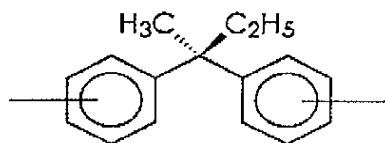
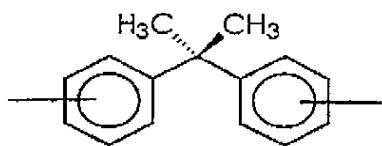
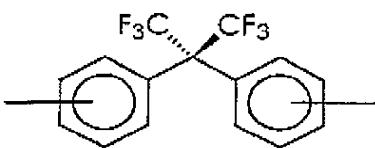
either (a) A is



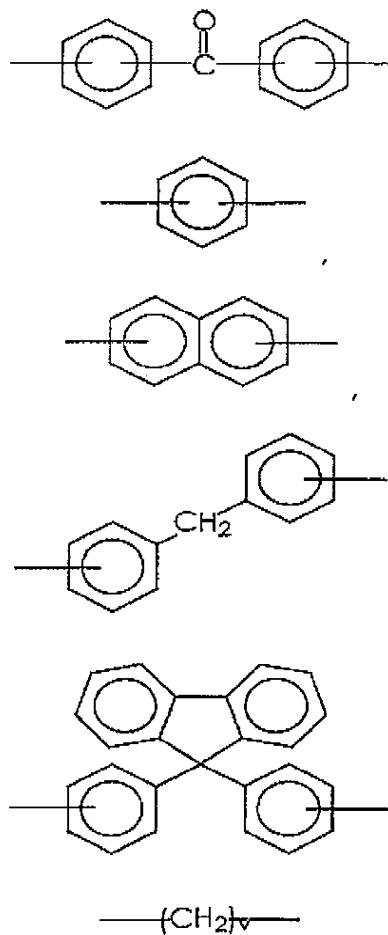
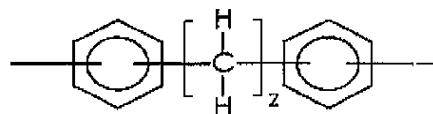
Application No. 10/036,469

or mixtures thereof, and B is

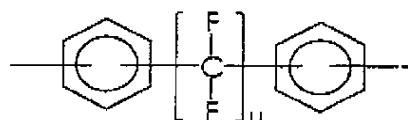
Application No. 10/036,469



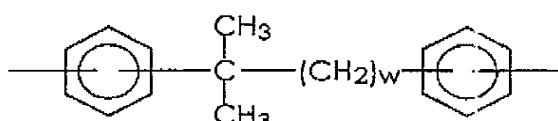
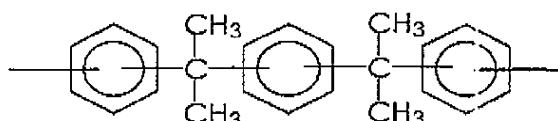
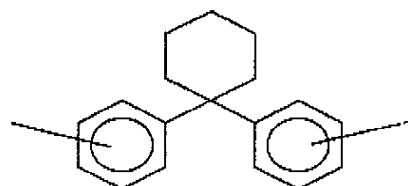
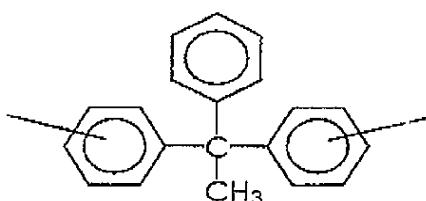
Application No. 10/036,469

wherein v is an integer of from 1 to about 20,wherein z is an integer of from 2 to about 20,

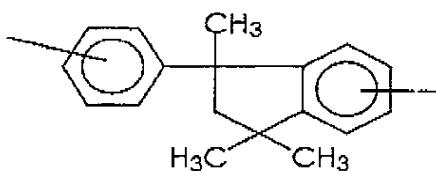
Application No. 10/036,469



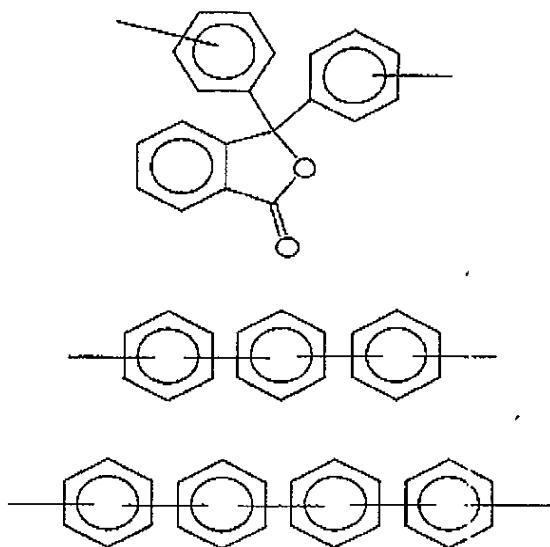
wherein u is an integer of from 1 to about 20,



wherein w is an integer of from 1 to about 20,



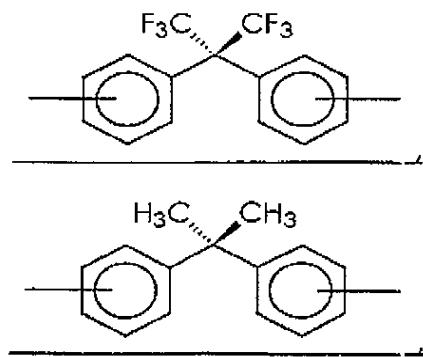
Application No. 10/036,469



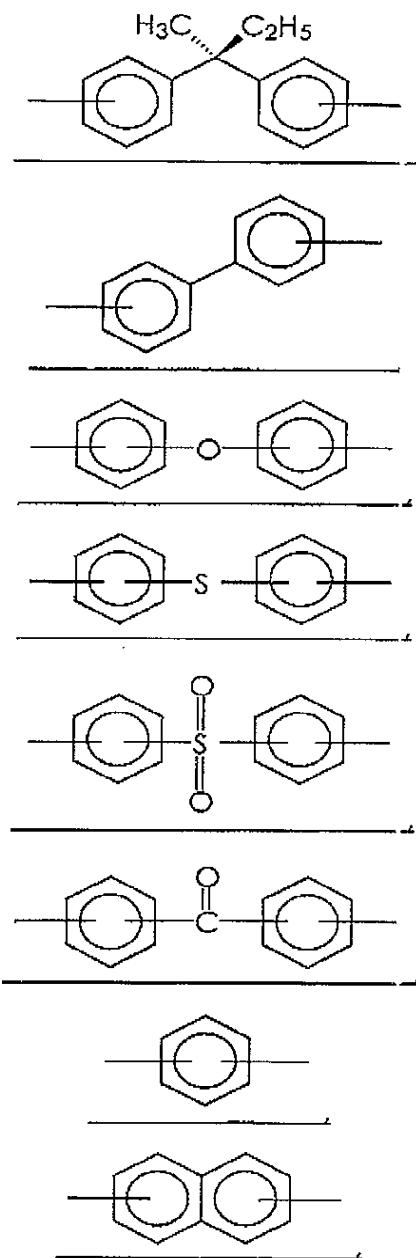
or mixtures thereof, or (b) A is



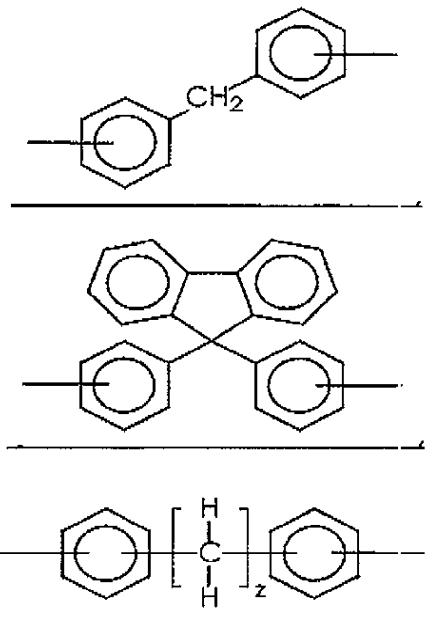
and B is



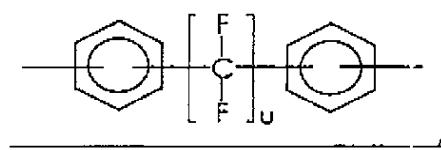
Application No. 10/036,469



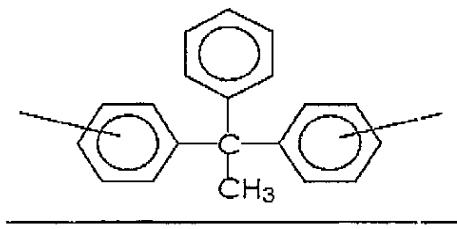
Application No. 10/036,469



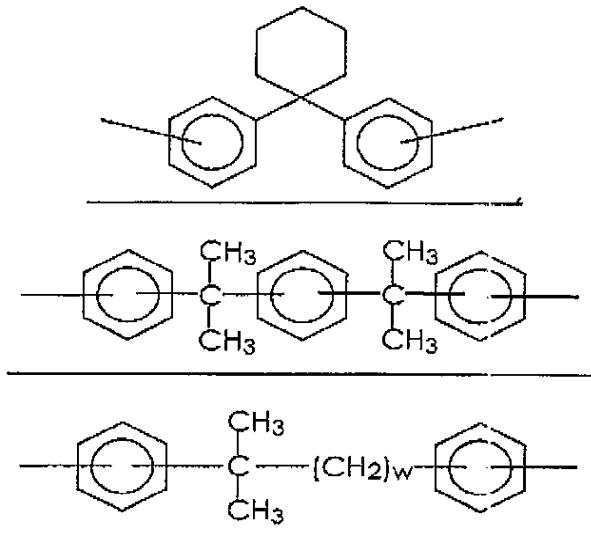
wherein z is an integer of from 2 to about 20,



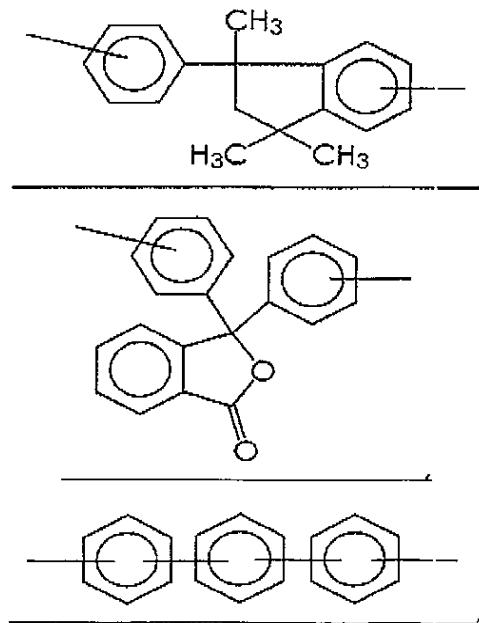
wherein u is an integer of from 1 to about 20,



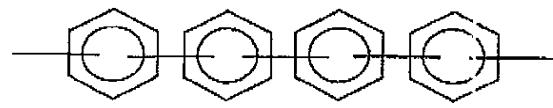
Application No. 10/036,469



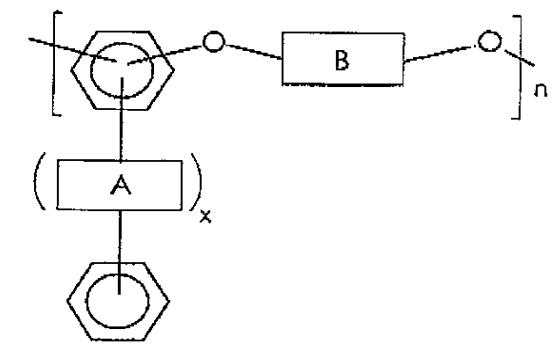
wherein w is an integer of from 1 to about 20.



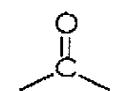
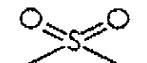
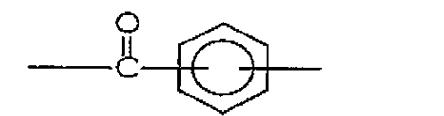
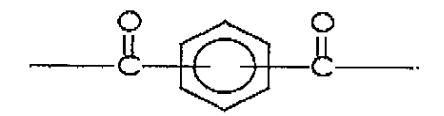
Application No. 10/036,469



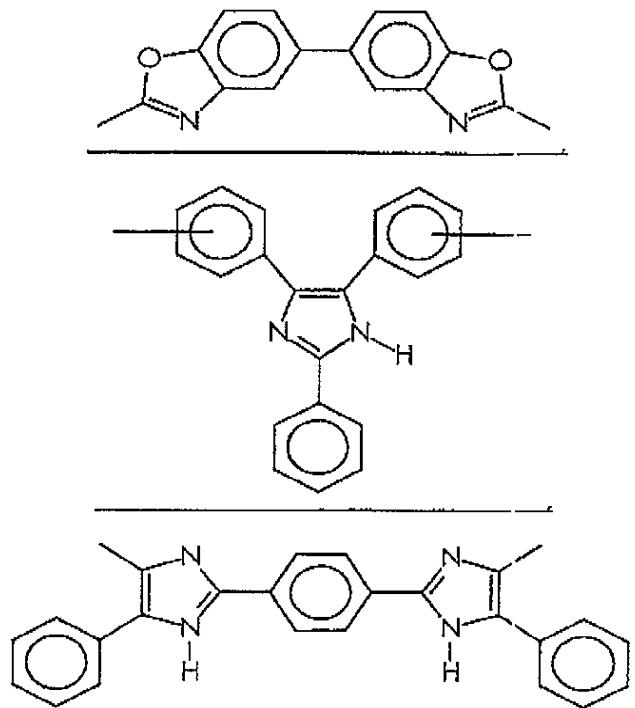
or mixtures thereof, and when the polymer backbone is of the formula



A is

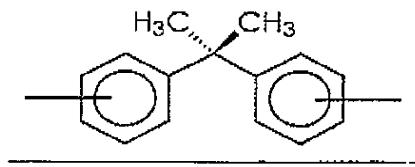
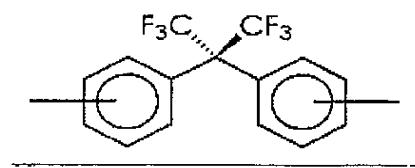


Application No. 10/036,469

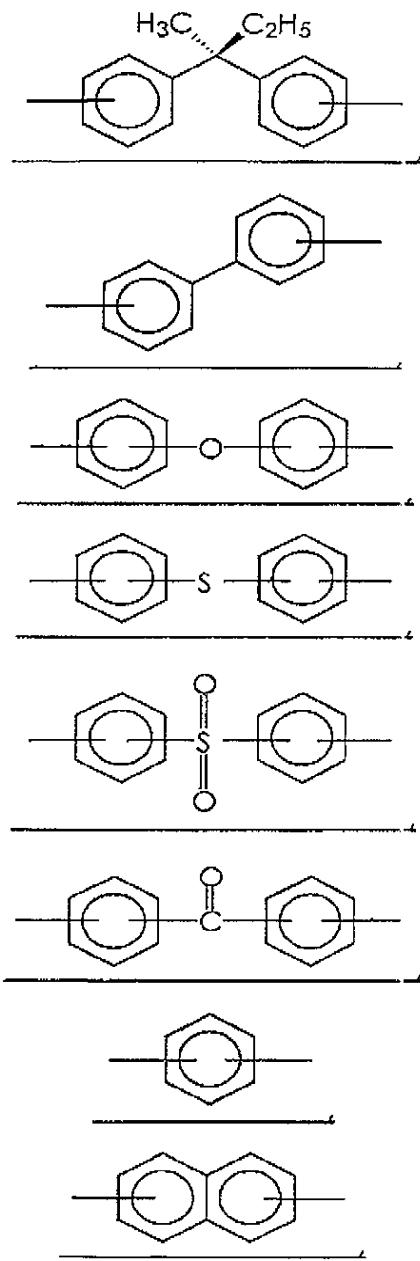


-O-
-C(CH₃)₂-

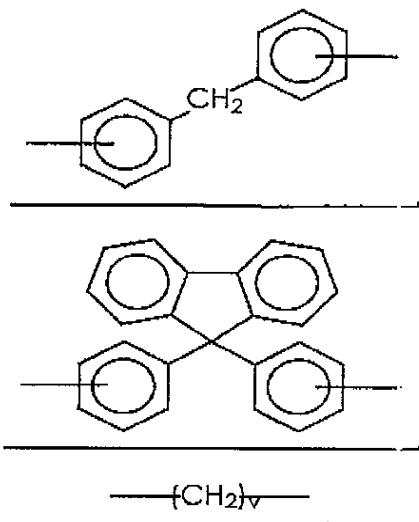
or mixtures thereof, and B is



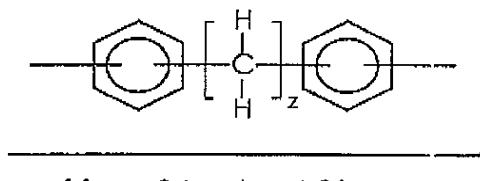
Application No. 10/036,469



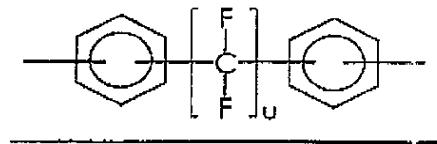
Application No. 10/036,469



wherein v is an integer of from 1 to about 20,

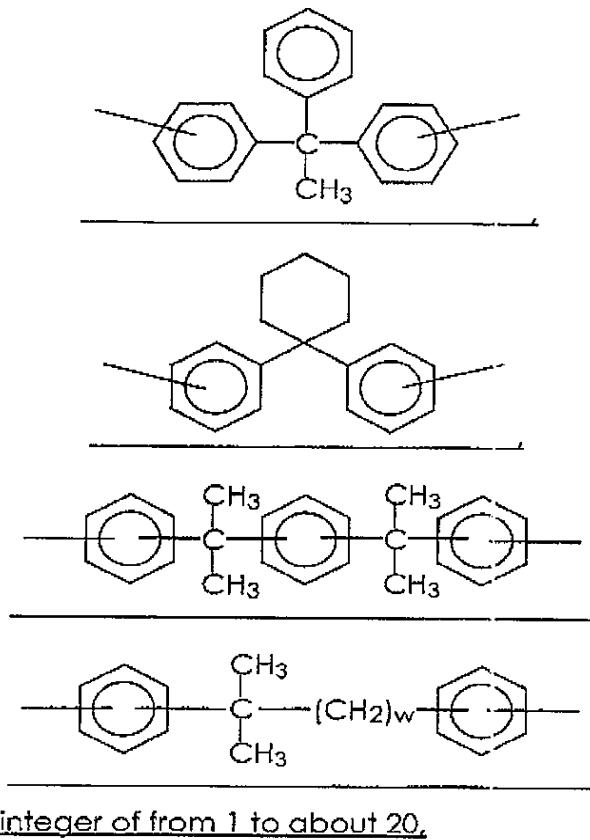


wherein z is an integer of from 2 to about 20,

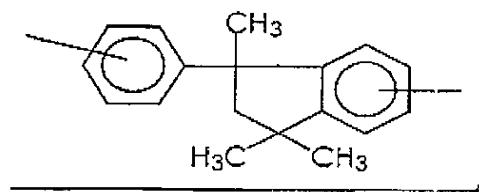


wherein u is an integer of from 1 to about 20,

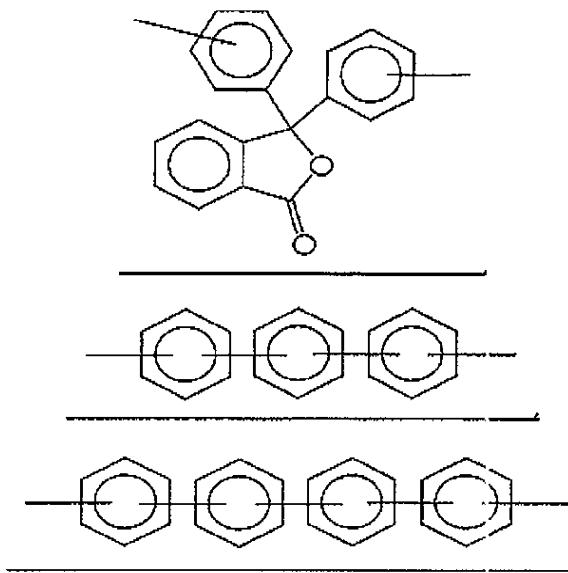
Application No. 10/036,469



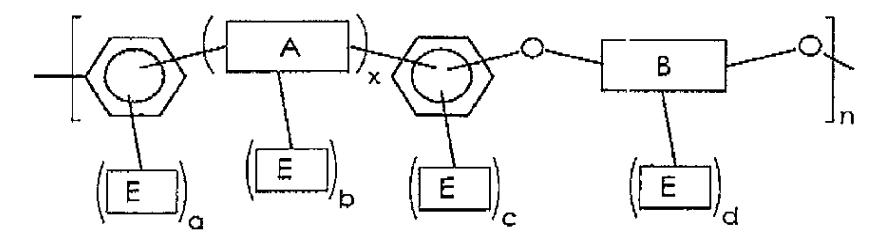
wherein w is an integer of from 1 to about 20.



Application No. 10/036,469

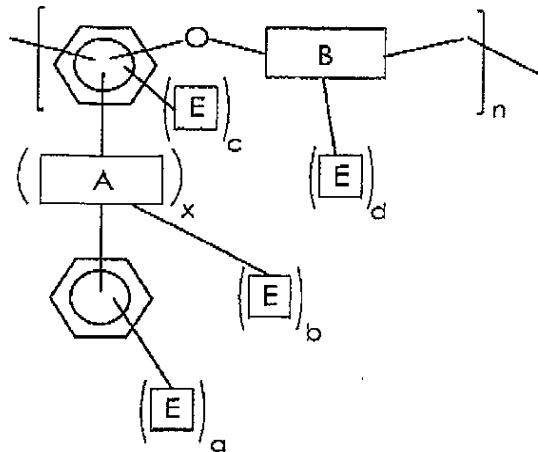


or mixtures thereof, and n is an integer representing the number of repeating monomer units, said crosslinked or chain extended polymer having been formed from a precursor polymer having epoxy groups contained on at least some of the monomer repeat units thereof, said precursor polymer being of the formula



or

Application No. 10/036,469



wherein "E" is an epoxy group and a, b, c, and d are each integers of 0, 1, 2, 3, or 4, provided that at least one of a, b, c, and d is equal to or greater than 1 in at least some of the monomer repeat units of the precursor polymer, said crosslinking or chain extension occurring having occurred through linking groups formed by a reaction between the epoxy groups contained on at least some of the monomer repeat units of the precursor polymer and amine groups on an amine curing agent.

Application No. 10/036,469

17. (Original) An ink jet printhead which comprises (i) an upper substrate with a set of parallel grooves for subsequent use as ink channels and a recess for subsequent use as a manifold, the grooves being open at one end for serving as droplet emitting nozzles, (ii) a lower substrate in which one surface thereof has an array of heating elements and addressing electrodes formed thereon, and (iii) a layer deposited on the surface of the lower substrate and over the heating elements and addressing electrodes and patterned to form recesses therethrough to expose the heating elements and terminal ends of the addressing electrodes, the upper and lower substrates being aligned, mated, and bonded together to form the printhead with the grooves in the upper substrate being aligned with the heating elements in the lower substrate to form droplet emitting nozzles, said layer comprising a crosslinked or chain extended polymer-containing composition according to claim 16.

18. (Original) A process according to claim 10 further comprising the step of causing the polymer to become crosslinked or chain extended through the photosensitivity-imparting groups.

19. (Original) A process according to claim 18 wherein crosslinking or chain extension is effected by heating the polymer to a temperature sufficient to enable the photosensitivity-imparting groups to form crosslinks or chain extensions in the polymer.

Application No. 10/036,469

20. (Original) A process according to claim 18 wherein crosslinking or chain extension is effected by exposing the polymer to actinic radiation such that the polymer in exposed areas becomes crosslinked or chain extended.

21. (Original) A process according to claim 20 wherein the polymer is exposed in an imagewise pattern such that the polymer in exposed areas becomes crosslinked or chain extended and the polymer in unexposed areas does not become crosslinked or chain extended, and wherein subsequent to exposure, the polymer in the unexposed areas is removed from the crosslinked or chain extended polymer, thereby forming an image pattern.

Application No. 10/036,469

22. (Original) A process according to claim 21 further comprising the steps of:

(a) depositing a layer comprising the polymer onto a lower substrate in which one surface thereof has an array of heating elements and addressing electrodes having terminal ends formed thereon, said polymer being deposited onto the surface having the heating elements and addressing electrodes thereon;

(b) exposing the layer to actinic radiation in an imagewise pattern such that the polymer in exposed areas becomes crosslinked or chain extended and the polymer in unexposed areas does not become crosslinked or chain extended, wherein the unexposed areas correspond to areas of the lower substrate having thereon the heating elements and the terminal ends of the addressing electrodes;

(c) removing the polymer from the unexposed areas, thereby forming recesses in the layer, said recesses exposing the heating elements and the terminal ends of the addressing electrodes;

(d) providing an upper substrate with a set of parallel grooves for subsequent use as ink channels and a recess for subsequent use as a manifold, the grooves being open at one end for serving as droplet emitting nozzles; and

(e) aligning, mating, and bonding the upper and lower substrates together to form a printhead with the grooves in the upper substrate being aligned with the heating elements in the lower substrate to form droplet emitting nozzles, thereby forming a thermal ink jet printhead.

Application No. 10/036,469

23. (Original) A process according to claim 10 further comprising the step of causing the polymer to become crosslinked or chain extended through the photosensitivity-imparting groups.

24. (Original) A process according to claim 23 wherein crosslinking or chain extension is effected by heating the polymer to a temperature sufficient to enable the photosensitivity-imparting groups to form crosslinks or chain extensions in the polymer.

25. (Original) A process according to claim 23 wherein crosslinking or chain extension is effected by exposing the polymer to actinic radiation such that the polymer in exposed areas becomes crosslinked or chain extended.

26. (Original) A process according to claim 25 wherein the polymer is exposed in an imagewise pattern such that the polymer in exposed areas becomes crosslinked or chain extended and the polymer in unexposed areas does not become crosslinked or chain extended, and wherein subsequent to exposure, the polymer in the unexposed areas is removed from the crosslinked or chain extended polymer, thereby forming an image pattern.

Application No. 10/036,469

27. (Original) A process according to claim 26 further comprising the steps of:

(a) depositing a layer comprising the polymer onto a lower substrate in which one surface thereof has an array of heating elements and addressing electrodes having terminal ends formed thereon, said polymer being deposited onto the surface having the heating elements and addressing electrodes thereon;

(b) exposing the layer to actinic radiation in an imagewise pattern such that the polymer in exposed areas becomes crosslinked or chain extended and the polymer in unexposed areas does not become crosslinked or chain extended, wherein the unexposed areas correspond to areas of the lower substrate having thereon the heating elements and the terminal ends of the addressing electrodes;

(c) removing the polymer from the unexposed areas, thereby forming recesses in the layer, said recesses exposing the heating elements and the terminal ends of the addressing electrodes;

(d) providing an upper substrate with a set of parallel grooves for subsequent use as ink channels and a recess for subsequent use as a manifold, the grooves being open at one end for serving as droplet emitting nozzles; and

(e) aligning, mating, and bonding the upper and lower substrates together to form a printhead with the grooves in the upper substrate being aligned with the heating elements in the lower substrate to form droplet emitting nozzles, thereby forming a thermal ink jet printhead.

12-16-2003 05:16pm From-XEROX

+5854235240

T-402 P.032/061 F-207

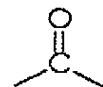
Application No. 10/036,469

28-29. (Canceled)

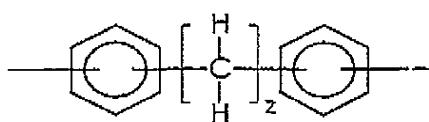
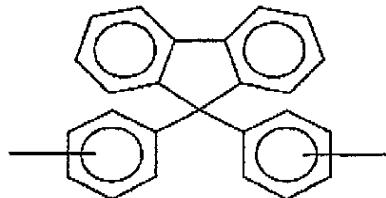
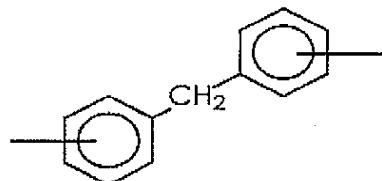
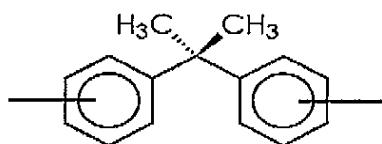
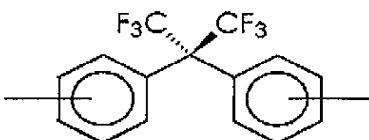
-31-

Application No. 10/036,469

30. (Original) A process according to claim 10 wherein
A is



and B is



Application No. 10/036,469

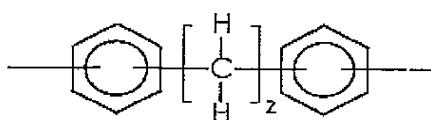
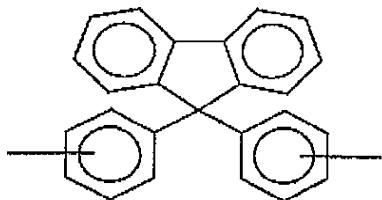
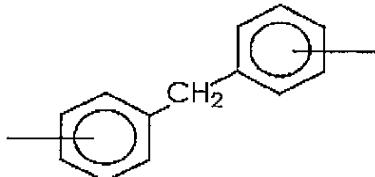
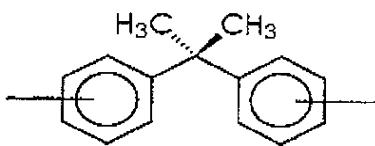
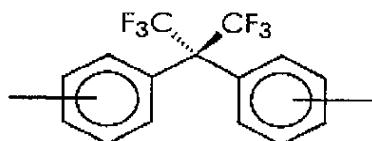
wherein z is an integer of from 2 to about 20, or a mixture thereof.

Application No. 10/036,469

31. (Original) A process according to claim 12 wherein A is



and B is



12-16-2003 05:17pm From-XEROX

+5854235240

T-402 P.036/061 F-207

Application No. 10/036,469

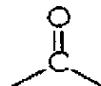
wherein z is an integer of from 2 to about 20, or a mixture thereof.

32. (Cancelled)

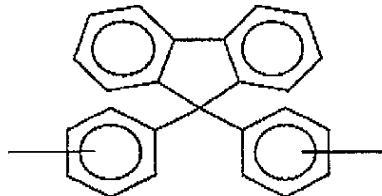
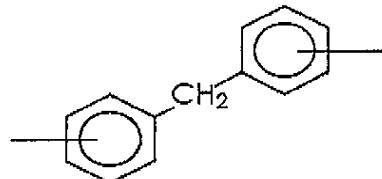
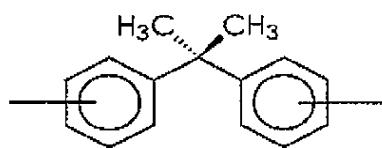
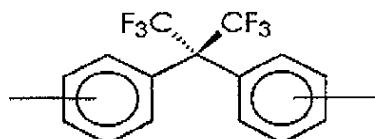
-35-

Application No. 10/036,469

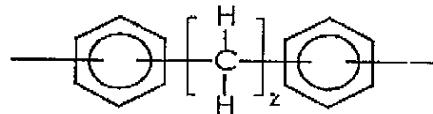
33. (Currently Amended) A composition according to
claim 16 wherein x is 1, A is



and B is



Application No. 10/036,469



wherein z is an integer of from 2 to about 20, or a mixture thereof.

34-37. (Canceled)

38. (Original) A process according to claim 10 wherein the polymer has end groups derived from the "A" groups of the polymer.

39. (Original) A process according to claim 10 wherein the polymer has end groups derived from the "B" groups of the polymer.

40. (Original) A process according to claim 12 wherein the polymer has end groups derived from the "A" groups of the polymer.

41. (Original) A process according to claim 12 wherein the polymer has end groups derived from the "B" groups of the polymer.

42-43. (Canceled)

44. (Original) A composition according to claim 16 wherein the polymer has end groups derived from the "A" groups of the polymer.

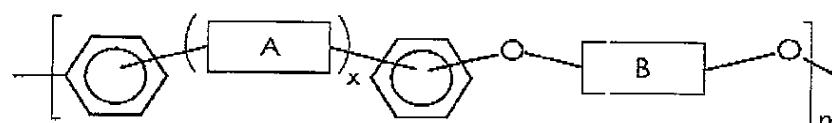
Application No. 10/036,469

45. (Original) A composition according to claim 16 wherein the polymer has end groups derived from the "B" groups of the polymer.

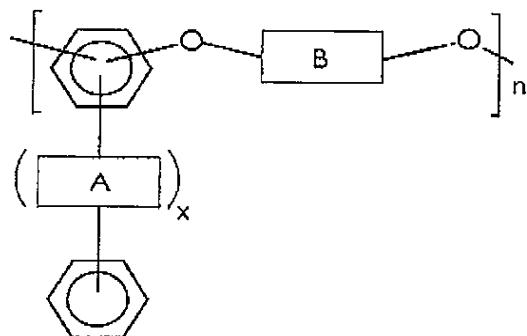
46. (Canceled)

Application No. 10/036,469

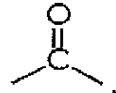
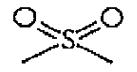
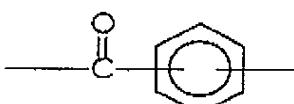
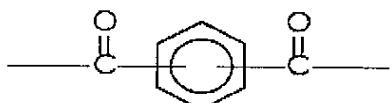
47. (Original) A process which comprises reacting a polymer containing at least some monomer repeat units with haloalkyl substituents thereon and of the formula



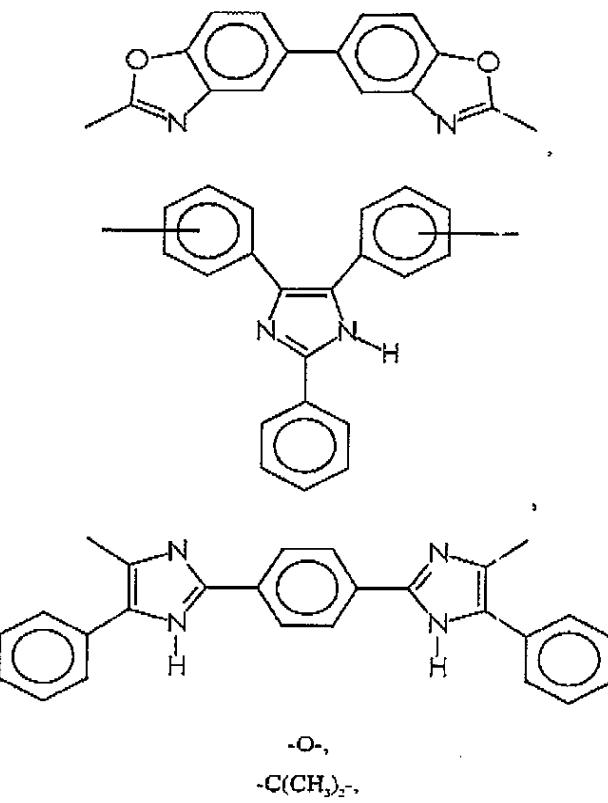
or



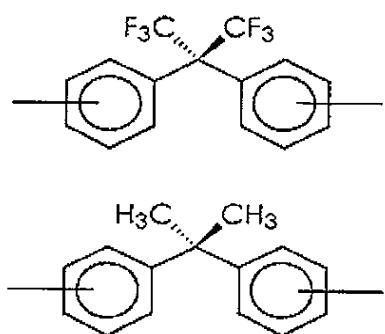
wherein x is an integer of 0 or 1, A is



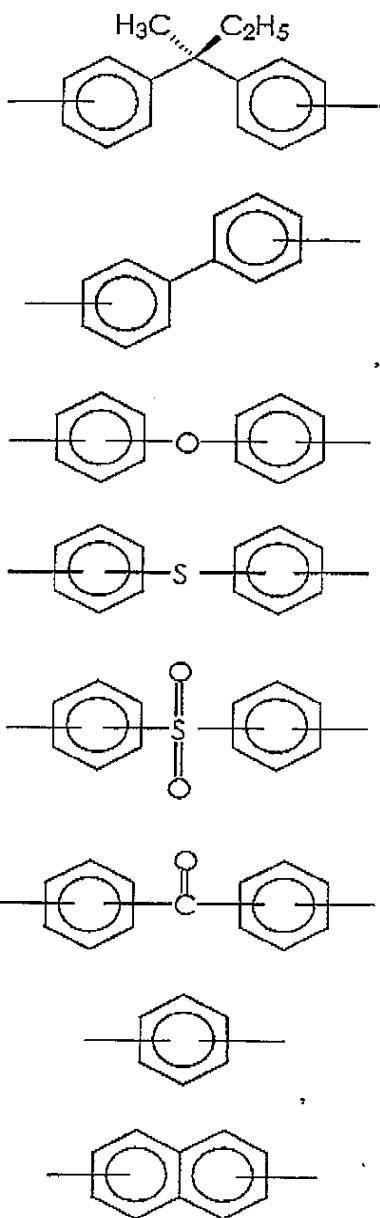
Application No. 10/036,469



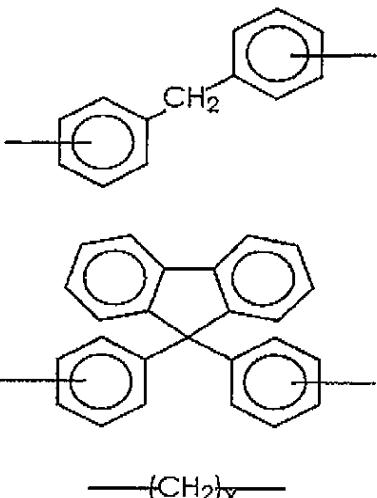
or mixtures thereof, B is



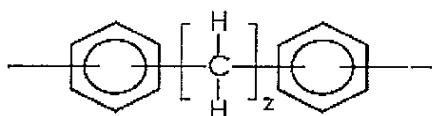
Application No. 10/036,469



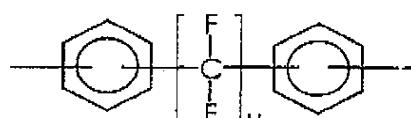
Application No. 10/036,469



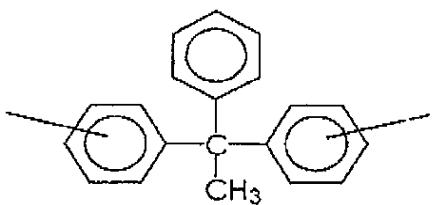
wherein v is an integer of from 1 to about 20,



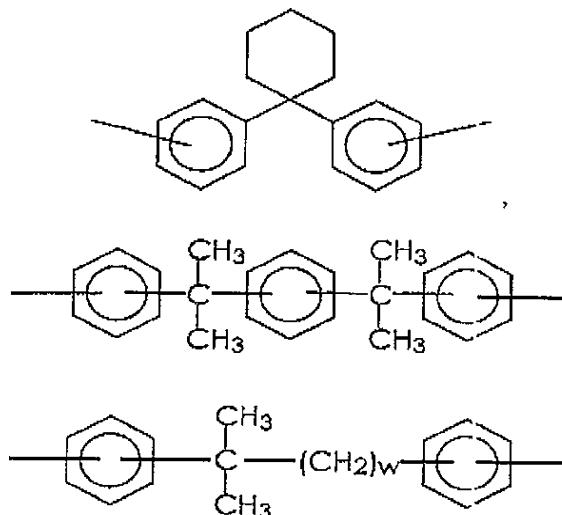
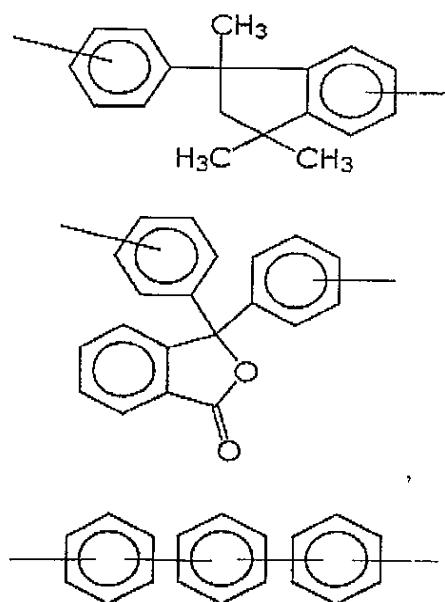
wherein z is an integer of from 2 to about 20,



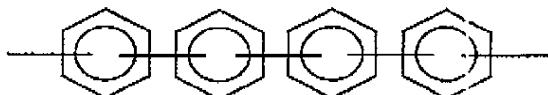
wherein u is an integer of from 1 to about 20,



Application No. 10/036,469

wherein w is an integer of from 1 to about 20,

Application No. 10/036,469



or mixtures thereof, and n is an integer representing the number of repeating monomer units, with an epoxy-group-containing alcohol salt, thereby forming a photopatternable polymer with epoxy functional groups corresponding to the selected salt.

48. (Original) A polymer prepared according to the process of claim 47.

49. (Original) A process according to claim 47 further comprising the step of causing the polymer to become crosslinked or chain extended through the photosensitivity-imparting groups.

50. (Original) A process according to claim 49 wherein crosslinking or chain extension is effected by heating the polymer to a temperature sufficient to enable the photosensitivity-imparting groups to form crosslinks or chain extensions in the polymer.

51. (Original) A process according to claim 49 wherein crosslinking or chain extension is effected by exposing the polymer to actinic radiation such that the polymer in exposed areas becomes crosslinked or chain extended.

Application No. 10/036,469

52. (Original) A process according to claim 51 wherein the polymer is exposed in an imagewise pattern such that the polymer in exposed areas becomes crosslinked or chain extended and the polymer in unexposed areas does not become crosslinked or chain extended, and wherein subsequent to exposure, the polymer in the unexposed areas is removed from the crosslinked or chain extended polymer, thereby forming an image pattern.

Application No. 10/036,469

53. (Original) A process according to claim 52 further comprising the steps of:

(a) depositing a layer comprising the polymer onto a lower substrate in which one surface thereof has an array of heating elements and addressing electrodes having terminal ends formed thereon, said polymer being deposited onto the surface having the heating elements and addressing electrodes thereon;

(b) exposing the layer to actinic radiation in an imagewise pattern such that the polymer in exposed areas becomes crosslinked or chain extended and the polymer in unexposed areas does not become crosslinked or chain extended, wherein the unexposed areas correspond to areas of the lower substrate having thereon the heating elements and the terminal ends of the addressing electrodes;

(c) removing the polymer from the unexposed areas, thereby forming recesses in the layer, said recesses exposing the heating elements and the terminal ends of the addressing electrodes;

(d) providing an upper substrate with a set of parallel grooves for subsequent use as ink channels and a recess for subsequent use as a manifold, the grooves being open at one end for serving as droplet emitting nozzles; and

(e) aligning, mating, and bonding the upper and lower substrates together to form a printhead with the grooves in the upper substrate being aligned with the heating elements in the lower substrate to form droplet emitting nozzles, thereby forming a thermal ink jet printhead.

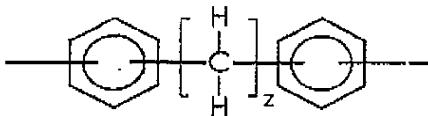
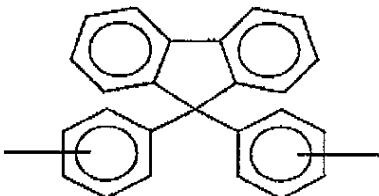
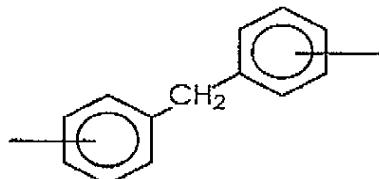
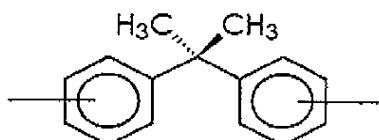
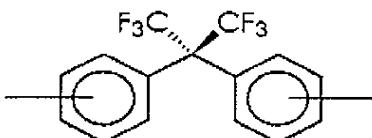
Application No. 10/036,469

54. (Original) A process according to claim 47 wherein

A is



and B is



Application No. 10/036,469

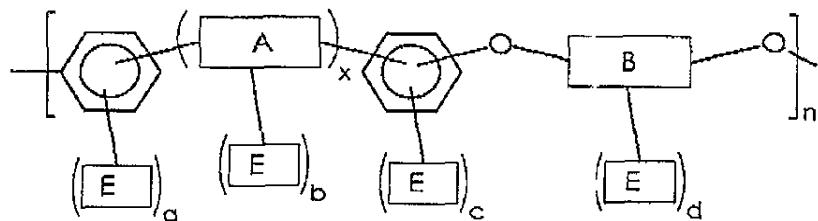
wherein z is an integer of from 2 to about 20, or a mixture thereof.

55. (Original) A process according to claim 47 wherein the polymer has end groups derived from the "A" groups of the polymer.

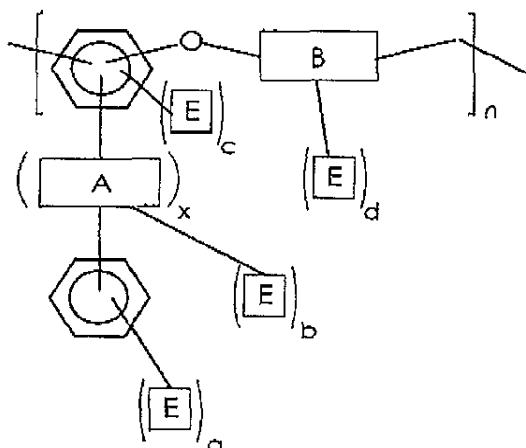
56. (Original) A composition according to claim 47 wherein the polymer has end groups derived from the "B" groups of the polymer.

Application No. 10/036,469

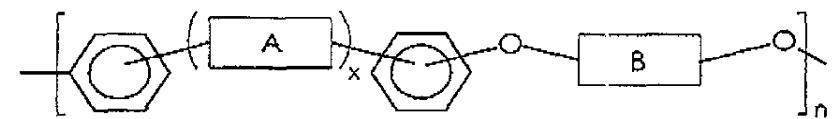
57. (Currently Amended) A composition according to
claim 16 wherein the precursor polymer of the formula



or

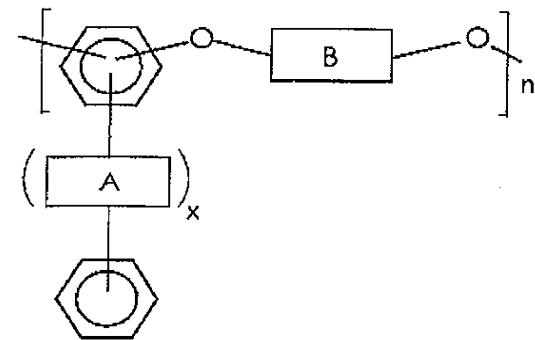


is prepared by substituting a preprecursor polymer of the formula



or

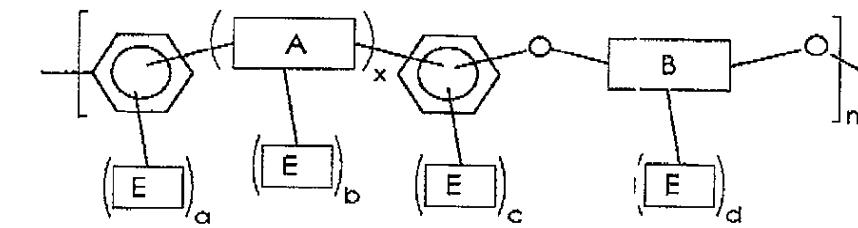
Application No. 10/036,469



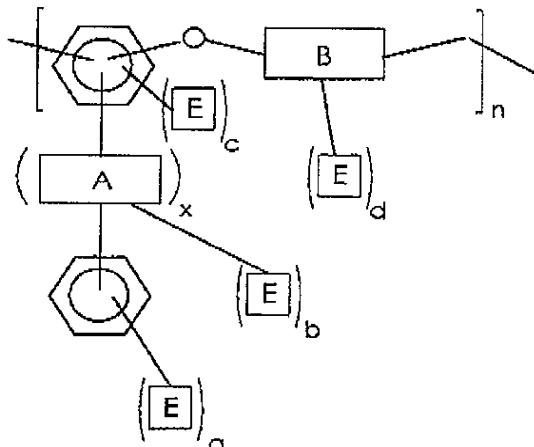
with epoxy groups, and wherein the value of n is such that the weight average molecular weight of the precursor polymer prior to crosslinking or chain extension is from about 1,000 to about 100,000.

Application No. 10/036,469

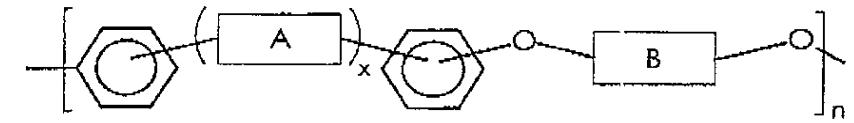
58. (Currently Amended) A composition according to
claim 16 wherein the precursor polymer of the formula



or

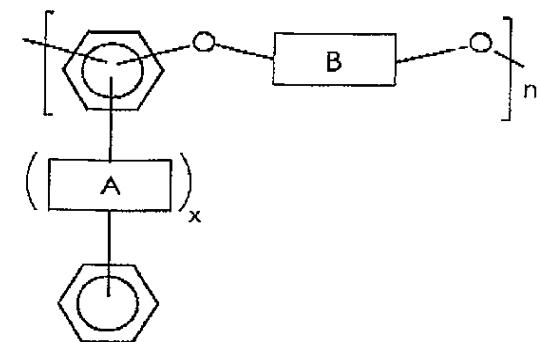


is prepared by substituting a preprecursor polymer of the formula



or

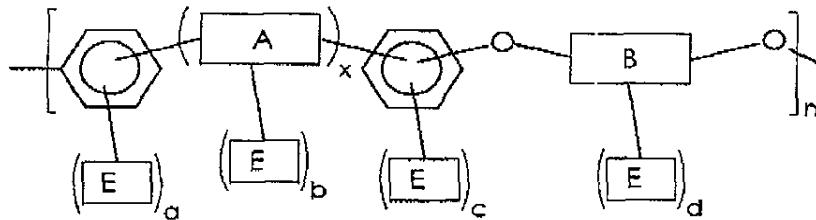
Application No. 10/036,469



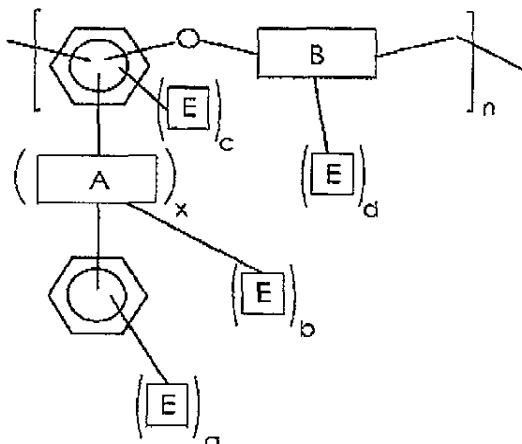
with epoxy groups, and wherein the value of n is such that the weight average molecular weight of the preprecursor polymer prior to crosslinking or chain extension is from about 1,000 to about 65,000.

Application No. 10/036,469

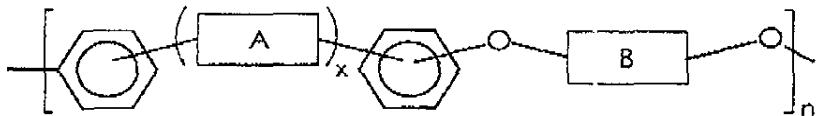
59. (Currently Amended) A composition according to claim 16 wherein the precursor polymer of the formula



or

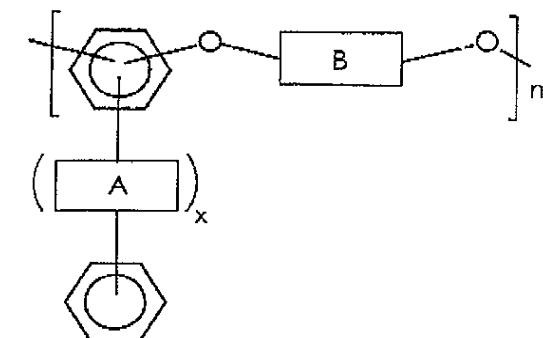


is prepared by substituting a preprecursor polymer of the formula



or

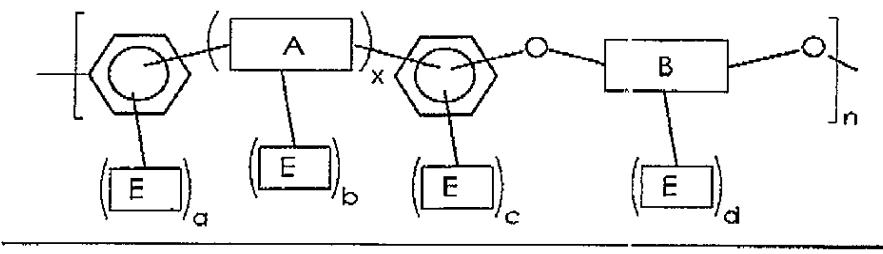
Application No. 10/036,469



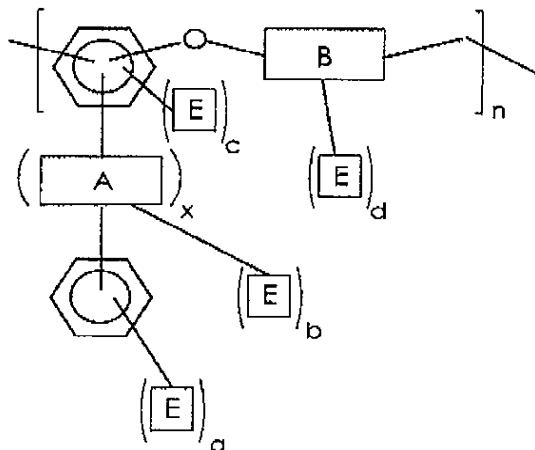
with epoxy groups, and wherein the value of n is such that the weight average molecular weight of the precursor polymer prior to crosslinking or chain extension is from about 1,000 to about 40,000.

Application No. 10/036,469

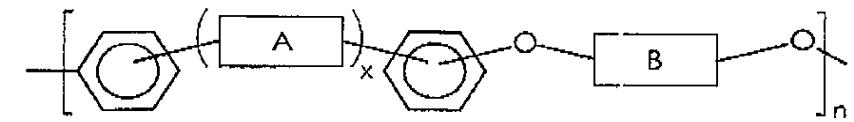
60. (Currently Amended) A composition according to claim 16 wherein the precursor polymer of the formula



or

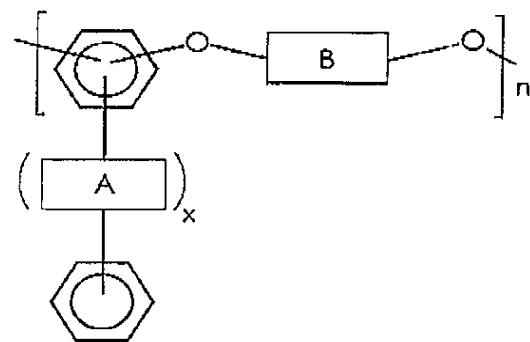


is prepared by substituting a preprecursor polymer of the formula



or

Application No. 10/036,469



with epoxy groups, and wherein the value of n is such that the weight average molecular weight of the precursor polymer prior to crosslinking or chain extension is from about 3,000 to about 25,000.

Application No. 10/036,469

61. (Previously presented) A composition according to claim 16 wherein n is an integer of from about 2 to about 70.

62. (Previously presented) A composition according to claim 16 wherein n is an integer of from about 5 to about 70.

63. (Previously presented) A composition according to claim 16 wherein n is an integer of from about 8 to about 50.

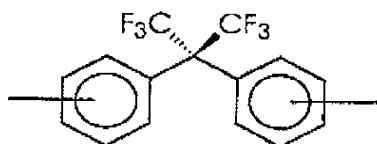
64. (Currently Amended) A composition according to claim 16 wherein the precursor polymer has a degree of substitution of on average from about 0.5 to about 2 photosensitivity-imparting-epoxy groups per monomer repeat unit.

65. (Currently Amended) A composition according to claim 16 wherein the precursor polymer has a degree of substitution of on average from about 0.5 to about 1.5 photosensitivity-imparting-epoxy groups per monomer repeat unit.

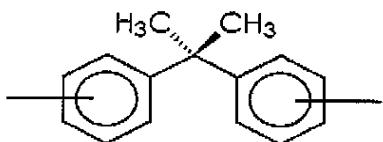
66. (Currently Amended) A composition according to claim 16 wherein the precursor polymer has a degree of substitution of from about 0.8 to about 1.3 milliequivalents of ~~allyl-ether-epoxy~~ groups per gram of precursor polymer.

Application No. 10/036,469

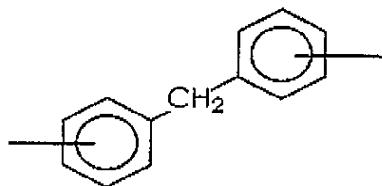
67. (Previously presented) A composition according to
claim 33 wherein B is



68. (Previously presented) A composition according to
claim 33 wherein B is

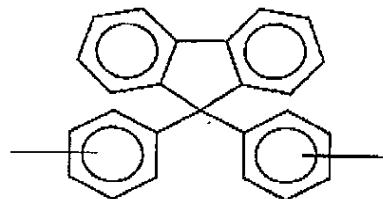


69. (Previously presented) A composition according to
claim 33 wherein B is

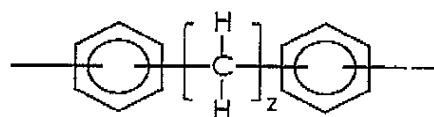


Application No. 10/036,469

70. (Previously presented) A composition according to claim 33 wherein B is



71. (Previously presented) A composition according to claim 33 wherein B is



wherein z is an integer of from 2 to about 20.